



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT

Group Art Unit: 1756

Examiner: S. Mohamedulla

COPY

TC 1700

INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER

JUL 10 2001

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Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Enclosed is an Information Disclosure Statement and accompanying form PTO-1449 for the above-identified patent application.

- ☒ No additional fee for submission of an IDS is required.
- ☐ The fee of \$180.00 (126) as set forth in 37 C.F.R. § 1.17(p) is also enclosed.
- ☒ A certification under 37 C.F.R. § 1.97(e) is also enclosed.
- ☐ A certification under 37 C.F.R. § 1.97(e), and the fee of \$180.00 (126) as set forth in 37 C.F.R. § 1.17(p) are also enclosed.
- ☐ Charge \$_____ to Deposit Account No. 02-4800 for the fee due.
- ☐ A check in the amount of \$_____ is enclosed for the fee due.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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